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in the second field plane 9 have an aperture obscuration almost independent of field height. If a mechanical shutter diaphragm with variable diameter is arranged in the aperture plane 29, the shutter blades can move on a curved surface in accordance with the curvature of the aperture plane. It is also possible to provide a plurality of flat mechanical diaphragms with variable diameter which can be inserted if required axially offset. The marginal rays 37 and 39, which emanate from the two field points 33 and 35 in the first field plane 7, go through the upper and lower margins of the aperture plane 29 39. The field point 33 is located on the optical axis OA, and the field point 35 is located on the upper margin of the field at a distance of 100 mm from the optical axis OA. Further illustrated for the field point 33 are the rays 41 which are just no longer vignetted by the mirror apertures. In the second field plane 9, they have an aperture angle of 18.4° , and so the aperture obscuration is 0.45. The ratio of the numerical aperture in the second field plane to the aperture obscuration is therefore 1.56. The mirror aperture 19 of the concave mirror 17 acts in a limiting fashion for the aperture obscuration in the first exemplary embodiment--.

On page 33, please amend the paragraph beginning with "In order to keep the aperture" as follows:

--In order to keep the aperture obscuration as low as possible, the concave mirrors 249 and 225 are arranged in the vicinity of the intermediate image 211, or of the further intermediate image 243. The axial distance between the concave mirror 249 and the intermediate image 211 is 50.0 mm, and likewise 50.0 mm between the concave mirror

401 by the micromirrors. The computer and control unit 477 is used to control the pump laser 457, the illuminating system 455, for the purpose of varying the pupil illumination, the controllable micromirror array 467 and the holding and positioning units 473 and 469.--